

UNITED STATES PATENT AND TRADEMARK OFFICE

UNITED STATES DEPARTMENT OF COMMERCE United States Patent and Trademark Office Address: COMMISSIONER FOR PATENTS P.O. Box 1450 Alexandria, Virginia 22313-1450 www.uspto.gov

APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.	
10/734,261	12/15/2003	Mitsugu Sato	H6808.0005/P005-A	1481	
	00/03/2004			EXAMINER	
DICKSTEIN SHAPIRO MORIN & OSHINSKY LLP 2101 L STREET NW			JOHNSTON, PHILLIP A		
	N, DC 20037-1526	*	ART UNIT	PAPER NUMBER	
			2881		
			DATE MAILED, 06/02/200		

Please find below and/or attached an Office communication concerning this application or proceeding.

	Application No.	Applicant(s)
Office Action Summans	10/734,261	SATO ET AL.
Office Action Summary	Examiner	Art Unit
	Phillip A Johnston	2881
The MAILING DATE of this communication app Period for Reply	ears on the cover sheet with the c	orrespondence address
A SHORTENED STATUTORY PERIOD FOR REPLY THE MAILING DATE OF THIS COMMUNICATION. - Extensions of time may be available under the provisions of 37 CFR 1.13 after SIX (6) MONTHS from the mailing date of this communication. - If the period for reply specified above is less than thirty (30) days, a reply If NO period for reply is specified above, the maximum statutory period we Failure to reply within the set or extended period for reply will, by statute, Any reply received by the Office later than three months after the mailing earned patent term adjustment. See 37 CFR 1.704(b).	within the statutory minimum of thirty (30) days ill apply and will expire SIX (6) MONTHS from	nely filed s will be considered timely. the mailing day of this communication.
Status		
1) Responsive to communication(s) filed on		
	action is non-final.	
3) Since this application is in condition for allowan		secution as to the merits is
closed in accordance with the practice under Ex	x parte Quayle, 1935 C.D. 11, 45	3 O.G. 213
Disposition of Claims		
4) ☐ Claim(s) 24-32 is/are pending in the application 4a) Of the above claim(s) is/are withdraw 5) ☐ Claim(s) is/are allowed. 6) ☐ Claim(s) 24-32 is/are rejected. 7) ☐ Claim(s) is/are objected to. 8) ☐ Claim(s) are subject to restriction and/or	n from consideration.	
Application Denom		
Application Papers		
9) The specification is objected to by the Examiner.		
10)⊠ The drawing(s) filed on <u>15 December 2003</u> is/are		
Applicant may not request that any objection to the di	rawing(s) be held in abeyance. See	37 CFR 1.85(a).
Replacement drawing sheet(s) including the correction 11) The oath or declaration is objected to by the Exa	on is required if the drawing(s) is objective.	ected to. See 37 CFR 1.121(d).
, <u> </u>	miner. Note the attached Office /	Action or form PTO-152.
Priority under 35 U.S.C. § 119	92.	
12) Acknowledgment is made of a claim for foreign p a) All b) Some * c) None of:	priority under 35 U.S.C. § 119(a)-	(d) or (f).
1.⊠ Certified copies of the priority documents	have been received	
2. Certified copies of the priority documents		n No
3. Copies of the certified copies of the priorit		
application from the International Bureau	(PCT Rule 17.2(a))	ani una radonal Stage
* See the attached detailed Office action for a list of		lk.*
		*
Attachment(s)		
) Notice of References Cited (PTO-892)	4) Interview Summary (F	PTO-413)
 Notice of Draftsperson's Patent Drawing Review (PTO-948) Information Disclosure Statement(s) (PTO-1449 or PTO/SB/08) Paper No(s)/Mail Date <u>5-24-2004</u>. 	Paper No(s)/Mail Date	e tent Application (PTO-152)
Patent and Trademark Office		×

Application/Control Number: 10/734,261

Art Unit: 2881

Detailed Action

Claims Rejection - 35 U.S.C. 102

Page 2

1. The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless -

(b) the invention was patented or described in a printed publication in this or a foreign country or in public use or on sale in this country, more than one year prior to the date of application for patent in the United States.

2. Claims 24-30, and 32 are rejected under 35 U.S.C. 102(b) as being anticipated by U.S. Patent No. 5,627;373, to Keese.

Keese (373) clearly discloses the following;

- (a) An electron beam alignment correction apparatus and method that includes a source, an alignment deflector, and a pattern recognition circuit 48 that computes the axis of beam distortion between successive images. Once this axis is determined, the control circuit generates astigmatism coil control signals for compressing the beam along such axis. The astigmatism control signal magnitude then is indexed and the process repeated iteratively until the axis of highest beam distortion is less than a threshold value. When such condition is reached, the electron beam is considered to be substantially radially uniform, as recited in claims 24,25,27, and 32. See Column 3, line 47-53; and Column 6, line 52-65.
 - (b) Pattern recognition circuit 48 analyzes the image of magnified boundary portion 68 and generates a signal IND for indicating the position of the image of boundary portion 68 in the field of view. A indicator signal IND is generated for each of

Application/Control Number: 10/734,261 Page 3

Art Unit: 2881

the extremes of the focus range. Pattern recognition circuit 48 outputs the respective indicator signals IND to control circuit 50. Control circuit 50 stores and compares portion 68 location indicator signals IND for positions in the field of view of magnified portion 68 at the extremes of the focus range. Control circuit 50 detects any translation of the magnified portion 68 and generates alignment coil control signals LC1 and LC2. Control circuit 50 provides signals LC1 and LC2 to alignment coils 22 for adjusting electron beam alignment, as recited in claim 26. See Column 6, line 52-65.

(c) Pattern recognition circuit 48 analyzes detector signal FD for imaged features of specimen S, such as position in the field of view and sharpness of the edge image. For example, in one embodiment pattern recognition circuit 48 determines the absolute value of the peak first derivative of the smoothed image intensity of each raster scan line and derives an average over all scan lines. This information is contained in signal IND provided to control circuit 50. Control circuit 50 stores and analyzes signals IND, and calculates corrections to beam alignment and astigmatism. Control circuit 50 generates control signals LC1 and LC2 for automatically correcting beam alignment, and generates control signal ASC for automatically correcting beam astigmatism, as recited in claims 28-30, and 32. See Column 5, line 37-53; and Column 8, line 3-39.

Art Unit: 2881

Claims Rejection – 35 U.S.C. 103

3. The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:

- (a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which the subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.
- 4. Claims 24-32 are rejected under 35 U.S.C. 103(a) as being unpatentable over U.S. Patent No. 5,627,373, to Keese, in view of Onoguchi, U.S. Patent No. 6,067,164.

Keese (373) as applied above discloses all the limitations of claims 24-32 but fails to teach the use of a two-dimensional Fourier transform to quantify the image, as recited in claim 31. However, Onoguchi (164) discloses an astigmatism correction apparatus for correcting an astigmatism in an electron optics device by adjusting a stigmater of a charged particle beam optical system in the electron optics device, comprising: a secondary particle signal extraction unit for extracting secondary particle signals resulting from a two-dimensional scan of a charged particle beam over a sample by the electron optics device; a Fourier transform unit for calculating a power spectrum by applying a two-dimensional Fourier transform to the secondary particle signals extracted by the secondary particle signal extraction unit; a binarization unit for binarizing the power spectrum calculated by the Fourier transform unit to obtain a binarized image; an axis extraction unit for obtaining a principal axis and an axis

Application/Control Number: 10/734,261

Art Unit: 2881

perpendicular to the principal axis of the binarized image obtained by the binarization unit; an astigmatism information calculation unit for determining an intensity and a direction of the astigmatism by obtaining a distance between two points at which a sample image region in the binarized image intersects with the principal axis and a distance between two points at which the sample image region in the binarized image intersect with the axis perpendicular to the principal axis; and an adjustment unit for adjusting the stigmater of the charged particle beam optical system according to the intensity and the direction of the astigmatism determined by the astigmatism information calculation unit. See Column 4, line 65-67; Column 5, line 1-25; Column 19, line 51-67; and Column 20, line 1-3.

Therefore it would have been obvious to one of ordinary skill in the art that the electron beam alignment correction apparatus and method of Keese (373) can be modified to use the Fourier transform in accordance with Onoguchi (164), to apply a two-dimensional Fourier transform to the secondary particle signals, thereby adjusting the stigmater of the charged particle beam optical system according to the intensity and the direction of the astigmatism determined by the astigmatism information calculation unit.

Application/Control Number: 10/734,261

Art Unit: 2881

Conclusion

5. Any inquiry concerning this communication or earlier communications should be directed to Phillip Johnston whose telephone number is (571) 272-2475. The examiner can normally be reached on Monday-Friday from 7:30 am to 4:00 pm. If attempts to reach the examiner by telephone are unsuccessful, the examiners supervisor John Lee can be reached at (571) 272-2477. The fax phone number for the organization where the application or proceeding is assigned is 703 872 9306.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

PJ

May 25, 2004

SUPERVISORY PATENT EXAMINER
TECHNOLOGY CENTER 2800

Page 6